L Number	Hits	Search Text	DB	Time stamp
1 Number	3	"20030059556" or 6537623.pn. or	USPAT;	2003/10/09 09:20
-		"20020192393"	US-PGPUB	2000, 20, 00 00 00
2	19		USPAT;	2003/10/09 09:29
-		Lachance.in. or Blain.in. or (Dalsa adj	US-PGPUB	
		semiconductor).as.) and ((PECVD or plasma		1
		or PCVD or (P-CVD)) with (silica or SiO2		
ĺ		or "SiO.sub.2" or SiO or SiOx or]	
		"SiO.sub.x" or (silicon adj \$20xide)))		*
3	8	(Ouellet or Grondin or Lachance or Blain	EPO; JPO;	2003/10/09 09:27
1		or (Dalsa adj semiconductor)) and ((PECVD	DERWENT;	
		or plasma or PCVD or (P-CVD)) same (silica	IBM_TDB	
ļ		or SiO2 or "SiO.sub.2" or SiO or SiOx or		
	_	"SiO.sub.x" or (silicon adj \$20xide)))		1 0000 /10 /00 00 10
4	0	427/569,574	USPAT;	2003/10/09 09:49
_	1202	(427/569,574).CCLS.	US-PGPUB USPAT;	2003/10/09 09:49
5	1302	(427/369,374).CCLS.	US-PGPUB	2003/10/09 09:49
6	444	(427/579).CCLS.	USPAT;	2003/10/09 09:49
0	444	(427/379).0013.	US-PGPUB	2003/10/03 03:49
7	317	(427/255.37).CCLS.	USPAT;	2003/10/09 09:49
1 ') , ,	(12., 200.07, 0000.	US-PGPUB	2300,20,03 03.43
8	2778	((427/163.2,167) or	USPAT;	2003/10/09 09:50
1		(385/129,130,131,132)).CCLS.	US-PGPUB	
9	2037	(427/372.2,397.7).CCLS.	USPAT;	2003/10/09 09:50
	1	100	US-PGPUB	
10	6553	((427/569,574).CCLS.) ((427/579).CCLS.)	USPAT;	2003/10/09 09:51
}	1	((427/255.37).CCLS.) (((427/163.2,167) or	US-PGPUB	
		(385/129,130,131,132)).CCLS.)		
		((427/372.2,397.7).CCLS.)		
11	1	((427/579).CCLS.) and (((427/163.2,167) or	USPAT;	2003/10/09 09:51
,		(385/129,130,131,132)).CCLS.) and	US-PGPUB	1
10]	((427/372.2,397.7).CCLS.)	TIODAM.	2003/10/09 09:51
12	11		USPAT; US-PGPUB	2003/10/09 09:51
13	10	((427/372.2,397.7).CCLS.) (((427/579).CCLS.) and	USPAT;	2003/10/09 11:26
13	10	((427/379).CCLS.) and ((427/372.2,397.7).CCLS.)) not	US-PGPUB	2003/10/09 11:26
	}	((427/579).CCLS.) and ((427/163.2,167)	35 13132	*
		or (385/129,130,131,132)).CCLS.) and	1	
}		((427/372.2,397.7).CCLS.))		
14	13	((427/579).CCLS.) and $((427/163.2,167)$ or	USPAT;	2003/10/09 09:52
		(385/129,130,131,132)).CCLS.)	US-PGPUB	
15	12	(((427/579).CCLS.) and (((427/163.2,167)	USPAT;	2003/10/09 09:55
		or (385/129,130,131,132)).CCLS.)) not	US-PGPUB	ļ
		(((427/579).CCLS.) and (((427/163.2,167)		
	(or (385/129,130,131,132)).CCLS.) and	1	
16	110	((427/372.2,397.7).CCLS.))	IICDAM -	2002/10/00 00-56
16	110	((427/579).CCLS.) and ((control\$4 or regulat\$3 or monitor\$3) near3 pressure)	USPAT; US-PGPUB	2003/10/09 09:56
17	106		USPAT;	2003/10/09 10:09
- '	1	monosilane or SiH4 or "SiH.sub.4") same	US-PGPUB	2000,10,00 10.09
1	1	(N20 or "N.sub.20" or "N.sub.2 0" or	00 10101	0
		(nitrous adj oxide)) same (N2 or "N.sub.2"		
ļ		or nitrogen))	ε,	
18	33		USPAT;	2003/10/09 11:45
1		((427/255.37).CCLS.) (((427/163.2,167) or	US-PGPUB	
		(385/129,130,131,132)).CCLS.)		
1	1	((427/372.2,397.7).CCLS.)) and ((silane or		
	1	monosilane or SiH4 or "SiH, sub.4") same		*
	1	(N20 or "N.sub.20" or "N.sub.2 0" or		
	*	(nitrous adj oxide)) same (N2 or "N.sub.2"		
		or nitrogen)) and ((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$20xide)]
		or silica or SiO2 or "SiO.sub.2" or SiOx		
	1	or SiO or "SiO.sub.x")) and (multiplex\$4	1	
		or demulitplex\$4 or Mux or Dmux or		
		wavequide or lightguide or (wave adj		
		guide) or (light adj guide))		
				

	,		TTGDTT	T 0000 /10 /00 11 00
19	10	(((427/569,574).CCLS.) ((427/579).CCLS.) ((427/255.37).CCLS.) (((427/163.2,167) or	USPAT; US-PGPUB	2003/10/09 11:33
		(385/129,130,131,132)).CCLS.)		
		((427/372.2,397.7).CCLS.)) and (control\$3	,	
		with (chamber or reactor or vacuum) with		
		pressure with (speed near3 pump\$3))	HODAM.	2003/10/09 11:38
20	3	(((427/569,574).CCLS.) ((427/579).CCLS.)	USPAT; US-PGPUB	2003/10/09 11:30
		((427/255.37).CCLS.) (((427/163.2,167) or (385/129,130,131,132)).CCLS.)	US-FGFUB	*
		((427/372.2,397.7).CCLS.)) and (high near3		
		(nitrogen or N2 or "N.sub.2") near3 ((flow		
		adj rate) or dilution))	}	}
21	3	(((427/569,574).CCLS.) ((427/579).CCLS.)	USPAT;	2003/10/09 11:39
21		((427/255.37).CCLS.) (((427/163.2,167) or	US-PGPUB	
		(385/129,130,131,132)).CCLS.)	}	
		((427/372.2,397.7).CCLS.)) and (high near5		
		(nitrogen or N2 or "N.sub.2") near5 ((flow	1	
		adj rate) or dilution))		·
22	0	(((427/569,574).CCLS.) ((427/579).CCLS.)	USPAT;	2003/10/09 11:39
ł		((427/255.37).CCLS.) (((427/163.2,167) or	US-PGPUB	
		(385/129,130,131,132)).CCLS.)		
	į	((427/372.2,397.7).CCLS.)) and (optimiz\$6		
		near5 (nitrogen or N2 or "N.sub.2") near5		
		((flow adj rate) or dilution))	IICDAM.	2003/10/09 11:51
23	6	((silane or monosilane or SiH4 or "SiH.sub.4") same (N2O or "N.sub.20" or	USPAT; US-PGPUB	2003/10/09 11:31
		"N.sub.2 O" or (nitrous adj oxide)) same	02-10108	
ĺ		(N2 or "N.sub.2" or nitrogen)) and		}
}		((plasma or PECVD or PCVD or P-CVD) with		
* *		((silicon adj \$20xide) or silica or SiO2		
İ	ł	or "SiO.sub.2" or SiOx or SiO or		ļ
		"SiO.sub.x")) and ((high\$2 or large\$3)	-)(-	
	1	near6 (nitrogen or N2 or "N.sub.2") near6		
1		(dilution or (flow adj rate)))		
24	151	((plasma or PECVD or PCVD or P-CVD) with	USPAT;	2003/10/09 12:05
}		((silicon adj \$20xide) or silica or SiO2	US-PGPUB	
		or "SiO.sub.2" or SiOx or SiO or		
		"SiO.sub.x")) and (waveguide or (wave adj		1
1		guide) or lightguide or (light adj guide)		
	ļ	or Dmux or mux or multiplex\$3 or demultiplex\$3) and ((control\$4 or		
		regulat\$4 or optimiz\$5) near4 pressure)		
		and ((anneal\$3 or heat\$3 or bake or baked		
		or baking or temperature) near5 (reduc\$5		
1		or minimiz\$5 or eliminat\$4 or contamin\$5		}
		or unwanted or expel\$4 or compound))	-	

25	140	(((plasma or PECVD or PCVD or P-CVD) with	USPAT;	2003/10/09 11:58
23	140	((silicon adj \$20xide) or silica or SiO2	US-PGPUB	2003/10/03 12:00
ł	9	or "SiO.sub.2" or SiOx or SiO or		
j		"SiO.sub.x")) and (waveguide or (wave adj		
		guide) or lightguide or (light adj guide)		
-	-00	or Dmux or mux or multiplex\$3 or		
		demultiplex\$3) and ((control\$4 or		
		regulat\$4 or optimiz\$5) near4 pressure)		
		and ((anneal\$3 or heat\$3 or bake or baked		
		or baking or temperature) near5 (reduc\$5		
		or minimiz\$5 or eliminat\$4 or contamin\$5		
		or unwanted or expel\$4 or compound))) not		1
		((((427/579).CCLS.) and ((silane or monosilane or SiH4 or "SiH.sub.4") same		
		(N2O or "N.sub.20" or "N.sub.2 0" or		
		(nitrous adj oxide)) same (N2 or "N.sub.2"		ł
		or nitrogen))) or ((((427/569,574).CCLS.)		
		((427/579).CCLS.) ((427/255.37).CCLS.)		`
		(((427/163.2,167) or		}
0	*	(385/129,130,131,132)).CCLS.)		
		((427/372.2,397.7).CCLS.)) and ((silane or	}	
		monosilane or SiH4 or "SiH.sub.4") same		
		(N2O or "N.sub.20" or "N.sub.2 0" or		
Ì		(nitrous adj oxide)) same (N2 or "N.sub.2"		
!		or nitrogen)) and ((plasma or PECVD or		}
!		PCVD or P-CVD) with ((silicon adj \$20xide)		}
		or silica or SiO2 or "SiO.sub.2" or SiOx	}	
		or SiO or "SiO.sub.x")) and (multiplex\$4		
100		or demulitplex\$4 or Mux or Dmux or	 	
		waveguide or lightguide or (wave adj		
26	204	guide) or (light adj guide))))	USPAT;	2003/10/09 12:10
26	324	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$20xide) or silica or SiO2	US-PGPUB	2003/10/03 12:10
		or "SiO.sub.2" or SiOx or SiO or	05-16105	1
0		"SiO.sub.x")) and (waveguide or (wave adj		
		guide) or lightquide or (light adj guide)		
ļ		or Dmux or mux or multiplex\$3 or		
	}	demultiplex\$3) and ((anneal\$3 or heat\$3 or	1	
		bake or baked or baking) near5 (reduc\$5 or	{	
		minimiz\$5 or eliminat\$4 or contamin\$5 or	1	
}]	unwanted or expel\$4 or compound))		
27	38		USPAT;	2003/10/09 12:06
	1	((427/255.37).CCLS.) (((427/163.2,167) or	US-PGPUB	
		(385/129,130,131,132)).CCLS.)	İ	
	ì	((427/372.2,397.7).CCLS.)) and (((plasma		
]	or PECVD or PCVD or P-CVD) with ((silicon adj \$20xide) or silica or SiO2 or		
		"SiO.sub.2" or SiOx or SiO or	1	
	}	"SiO.sub.x")) and (waveguide or (wave adj		
ļ		quide) or lightguide or (light adj guide)		
ĺ	1	or Dmux or mux or multiplex\$3 or		
		demultiplex\$3) and ((anneal\$3 or heat\$3 or		
		bake or baked or baking) near5 (reduc\$5 or		
1	1	minimiz\$5 or eliminat\$4 or contamin\$5 or		
		unwanted or expel\$4 or compound)))		
28	3	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	EPO; JPO;	2003/10/09 12:10
]]	((silicon adj \$20xide) or silica or SiO2	DERWENT;	
	1	or "SiO.sub.2" or SiOx or SiO or	IBM_TDB	
1	1	"SiO.sub.x")) and (waveguide or (wave adj		
		guide) or lightguide or (light adj guide)		
1		or Dmux or mux or multiplex\$3 or demultiplex\$3) and ((anneal\$3 or heat\$3 or		
)]	bake or baked or baking) near5 (reduc\$5 or		
	1	minimiz\$5 or eliminat\$4 or contamin\$5 or	1	
	}	unwanted or expel\$4 or compound))		
	<u> </u>	1	<u> </u>	



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Day: Thursday Date: 10/9/2003

Time: 09:08:02

Inventor Name Search Result

Your Search was:

Last Name = OUELLET

First Name = LUC

		G	D . T. 1		T
Application# 60447019	Not			FABRICATION OF	Inventor Name OUELLET, LUC
	Issued			ADVANCED SILICON-BASED MEMS	
60415782	Not Issued	020	10/04/2002	WAFER LEVEL PACKAGING TECHNIQUE FOR MEMS DEVICES	OUELLET, LUC
10459619	Not Issued	020	06/12/2003	METHOD OF FABRICATING SILICON-BASED MEMS DEVICES	OUELLET, LUC
10410158	Not Issued	019		FABRICATION OF ADVANCED SILICON-BASED MEMS DEVICES	OUELLET, LUC
10310814	Not Issued	030	12/06/2002	WAFER LEVEL PACKAGING TECHNIQUE FOR MICRODEVICES	OUELLET, LUC
10226189	Not Issued	041	08/23/2002	FABRICATION OF MEMS DEVICES WITH SPIN-ON GLASS	OUELLET, LUC
10153593	Not Issued	030	05/24/2002	FABRICATION OF MICROSTRUCTURES WITH VACUUM-SEALED CAVITY	OUELLET, LUC
10120528	6635509	150	04/12/2002	WAFER-LEVEL MEMS PACKAGING	OUELLET, LUC
10101622	Not Issued	030	03/21/2002	METHOD OF MAKING PHOTONIC DEVICES WITH SOG INTERLAYER	OUELLET, LUC
10059117	Not Issued	071	01/31/2002	METHOD OF PREVENTING CRACKING IN OPTICAL QUALITY SILICA LAYERS	OUELLET, LUC
09987829	Not Issued	095	11/16/2001	METHOD OF MAKING SPECULAR INFRARED MIRRORS FOR USE IN OPTICAL DEVICES	OUELLET, LUC
09973778	Not Issued	030	10/11/2001	METHOD OF REDUCING STRESS-INDUCED MECHANICAL PROBLEMS IN	OUELLET, LUC

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				OPTICAL COMPONENTS	
09964472	Not Issued	080	09/28/2001	VOLTAGE BIPOLAR/CMOS/DMOS (BCD) DEVICES	OUELLET, LUC
09956916	Not Issued	071	09/21/2001	METHOD OF DEPOSITING AN OPTICAL QUALITY SILICA FILM BY PECVD	OUELLET, LUC
09923367	6555441	150		METHOD OF ALIGNING STRUCTURES ON OPPOSITE SIDES OF A WAFER	OUELLET, LUC
09910795	Not Issued	041	07/24/2001	MICRO-FLUIDIC DEVICES	OUELLET, LUC
09867662	Not Issued	030	05/31/2001	METHOD OF DEPOSITING OPTICAL FILMS	OUELLET, LUC
09842836	6602791	150	04/27/2001	MANUFACTURE OF INTEGRATED FLUIDIC DEVICES	OUELLET, LUC
09833711	Not Issued	030	04/13/2001	OPTICAL QUALITY SILICA FILMS	OUELLET, LUC
09799496	6537623	150	03/07/2001	MANUFACTURE OF SILICA WAVEGUIDES WITH MINIMAL ABSORPTION	OUELLET, LUC
09799491	Not Issued	080	03/07/2001	METHOD OF MAKING A FUNCTIONAL DEVICE WITH DEPOSITED LAYERS SUBJECT TO HIGH TEMPERATURE ANNEAL	OUELLET, LUC
09679331	Not Issued	083	10/04/2000	COMBINATORIAL SYNTHESIS OF LIBRARIES OF MACROCYCLIC COMPOUNDS USEFUL IN DRUG DISCOVERY	OUELLET, LUC
09526569	6306683	150	03/16/2000	METHOD OF FORMING A FLIP CHIP ASSEMBLY, AND A FLIP CHIP ASSEMBLY FORMED BT THE METHOD	OUELLET, LUC
09357241	Not Issued	161	07/19/1999	SUBSTRATE PROCESSING APPARATUS WITH NON- AVAPOABLE GETTER PUMP	OUELLET, LUC
09314105	6083805	150	05/19/1999	METHOD OF FORMING CAPACITORS IN A SEMICONDUCTOR DEVICE	OUELLET, LUC
09236101	6268620	150	01/25/1999	METHOD OF FORMING CAPACITORS ON INTEGRATED CIRCUIT	OUELLET, LUC
09010191	6133060	150	01/21/1998	METHOD OF PROTECTING LIGHT SENSITIVE REGIONS	OUELLET, LUC

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				OF INTEGRATED CIRCUITS	
08979956	6127266	150	11/26/1997	STABILIZATION OF THE INTERFACE BETWEEN TIN AND A1 ALLOYS	OUELLET, LUC
08794441	6074946	150	02/04/1997	INTEGRATED PROCESSING FOR AN ETCH MODULE USING A HARD MASK TECHNIQUE	OUELLET, LUC
08666257	5778682	150	11	REACTIVE PVD WITH NEG PUMP	OUELLET, LUC
08666256	5935395	150	06/20/1996	SUBSTRTAE PROCESSING APPARATUS WITH NON- EVAPORABLE GETTER PUMP	OUELLET, LUC
08562575	Not Issued	161	11/24/1995	SUBSTRATE PROCESSING APPARATUS WITH NON- EVAPORABLE GETTER PUMP	OUELLET, LUC
08555325	Not Issued	161	11/08/1995	SUBSTRATE PROCESSING APPARATUS WITH NON- EVAPORABLE GETTER PUMP	OUELLET, LUC
08543497	5747361	150	10/16/1995	STABILIZATION OF THE INTERFACE BETWEEN ALUMINUM AND TITANIUM NITRIDE	OUELLET, LUC
08538857	5816821	150	10/04/1995	BILINGUAL EDUCATIONAL DOLLS	OUELLETTE , LUCY A.
08206024	Not Issued	161	II :	CURING AND PASSIVATION OF SPIN-ON-GLASSES BY A PLASMA PROCESS, AND PRODUCT PRODUCED THEREBY	OUELLET, LUC M.
08196078	5541445	150	02/25/1994	HIGH PERFORMANCE PASSIVATION FOR SEMICONDUCTOR DEVICES	OUELLET, LUC
08140080	Not Issued	166	06/15/1994	STABILIZATION OF THE INTERFACE BETWEEN ALUMINUM AND TITANIUM NITRIDE	OUELLET, LUC
08078166	5447613	150	06/21/1993	PREVENTING OF VIA POISONING BY GLOW DISCHARGE INDUCED DESORPTION	OUELLET, LUC
08049142	Not Issued	161	11	BILINGUAL EDUCATIONAL DOLLS	OUELLETTE , LUCY A.
08039485	5457073	150	04/30/1993	MULTI-LEVEL INTERCONNECTION CMOS DEVICES WITH SOG	OUELLET, LUC

h e eb cgbe f

07965264	5470798	150	01/26/1993	MOISTURE-FREE SOG PROCESS	OUELLET, LUC
07962214	5364818	150	01/26/1993	SOG WITH MOISTURE RESISTANT PROTECTIVE CAPPING LAYER	OUELLET, LUC
07930615	5320983	150	09/30/1992	SPIN-ON GLASS PROCESSING TECHNIQUE FOR THE FABRICATION OF SEMICONDUCTOR DEVICES	OUELLET, LUC
07817469	Not Issued	166	01/03/1992	CURING AND PASSIVATION OF SPIN ON GLASSES BY A PLASMA PROCESS, AND PRODUCT PRODUCED THEREBY	OUELLET , LUC M.
07794789	5270267	150	11/19/1991	CURING AND PASSIVATION OF SPIN ON GLASSES BY A PLASMA PROCESS, AND PRODUCT PRODUCED THEREBY	OUELLET , LUC M.
07359626	Not Issued	166	05/31/1989	CURING AND PASSIVATION OF SPIN ON GLASSES BY A PLASMA PROCESS, AND PRODUCT PRODUCED THEREBY	OUELLET , LUC M.
07250537	Not Issued	161	09/29/1988	PIPET DISPENSER	OUELLETTE , LUCILLE A.
07217718	4870829	150	07/11/1988	BIOLOGICAL FREEZING APPARATUS	OUELLETTE , LUCILLE A.
07156942	Not Issued	161	02/18/1988	PIPETTE STORAGE AND DISPENSING CONTAINER OR SIMILAR ARTICLE	OUELLETTE , LUCILLE A.

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	Last Name	First Name	
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Inventor Name Search Result

Your Search was:

Last Name = GRONDIN

First Name = MANUEL

Application#	Patent#	Status	Date Filed	Title	Inventor Name
09867662	Not Issued	030		METHOD OF DEPOSITING OPTICAL FILMS	GRONDIN, MANUEL
09833711	Not Issued	030	1	OPTICAL QUALITY SILICA FILMS	GRONDIN, MANUEL
<u>09799496</u>	6537623	150		MANUFACTURE OF SILICA WAVEGUIDES WITH MINIMAL ABSORPTION	GRONDIN, MANUEL

Inventor Search Completed: No Records to Display.

Last Name **First Name Search Another: Inventor** GRONDIN MANUEL Search

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Day: Thursday Date: 10/9/2003

Time: 09:10:23

Inventor Name Search Result

Your Search was:

Last Name = LACHANCE

First Name = JONATHAN

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10059117	Not	071	01/31/2002		LACHANCE,
-	Issued		e a	CRACKING IN OPTICAL QUALITY SILICA LAYERS	JONATHAN
09973778	Not Issued	030	10/11/2001	METHOD OF REDUCING STRESS-INDUCED MECHANICAL PROBLEMS IN OPTICAL COMPONENTS	LACHANCE, JONATHAN
09956916	Not Issued	071		METHOD OF DEPOSITING AN OPTICAL QUALITY SILICA FILM BY PECVD	LACHANCE, JONATHAN
09867662	Not Issued	030		METHOD OF DEPOSITING OPTICAL FILMS	LACHANCE, JONATHAN
09833711	Not Issued	030		1	LACHANCE, JONATHAN

Inventor Search Completed: No Records to Display.

	Last Name	First Name	
Search Another: Inventor	LACHANCE	JONATHAN	Search

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Time: 09:10:47

Inventor Name Search Result

Your Search was:

Last Name = BLAIN

First Name = STEPHANE

Application#	Patent#	Status	Date Filed	Title	Inventor Name
09867662	Not Issued	030		METHOD OF DEPOSITING OPTICAL FILMS	BLAIN, STEPHANE
09833711	Not Issued	030	04/13/2001	OPTICAL QUALITY SILICA FILMS	BLAIN, STEPHANE
09775465	6598610	150	02/05/2001	METHOD OF DEPOSITING A THICK DIELECTRIC FILM	BLAIN, STEPHANE
09314105	6083805	150		METHOD OF FORMING CAPACITORS IN A SEMICONDUCTOR DEVICE	BLAIN, STEPHANE

Inventor Search Completed: No Records to Display.

Search Another: Inventor	Last Name	First Name	
	BLAIN	STEPHANE	Search

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